

# Gasonics L3500

The Gasonics L3500 plasma system is designed for ashing and cleaning semiconductor wafers. Gasonics L3500 does this by creating monatomic oxygen, the active specie, which chemically reacts with the photoresist on the surface of the wafer.

[Description](#)

## Description

**Model:** Gasonics L3500 Asher semiconductor process equipment

**Category:** [Plasma Asher](#)

**Original Equipment Manufacturer:** [Gasonics](#)

**Robot upgrade:** HINE Hatm 5.0 atmospheric robot arm

**Wafer Size:** 6 inch configuration.

Process Gasses: O2 and N2

estimated weight: 200kg